

Uploading C:\Program Files\Stnexp\Queries\10080319-1.str

L2 STRUCTURE UPLOADED

=> que L2 AND L1

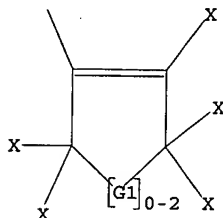
L3 QUE L2 AND L1

=> d

L3 HAS NO ANSWERS

L1 SCR 2067

L2 STR



G1 CF2,CBr2,CI2

Structure attributes must be viewed using STN Express query preparation.
L3 QUE ABB=ON PLU=ON L2 AND L1

=> s l3 sss sam

SAMPLE SEARCH INITIATED 11:27:34 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 91 TO ITERATE

100.0% PROCESSED 91 ITERATIONS

7 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**

PROJECTED ITERATIONS: 1248 TO 2392

PROJECTED ANSWERS: 7 TO 298

L4 7 SEA SSS SAM L2 AND L1

=> d

L4 ANSWER 1 OF 7. REGISTRY COPYRIGHT 2003 ACS on STN

RN 430427-86-4 REGISTRY

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester,
polymer with 2,5-furandione and octafluorocyclopentene (9CI) (CA INDEX
NAME)

MF (C12 H18 O2 . C5 F8 . C4 H2 O3)x

CI PMS

PCT Polyether, Polyvinyl

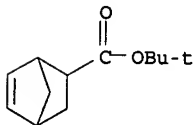
SR CA

LC STN Files: CA, CAPLUS

CM 1

CRN 154970-45-3

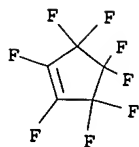
CMF C12 H18 O2



CM 2

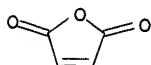
CRN 559-40-0

CMF C5 F8



CM 3

CRN 108-31-6
CMF C4 H2 O3



1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> FIL CAPLUS HCAPLUS USPATFUL
COST IN U.S. DOLLARS

SINCE FILE ENTRY	TOTAL SESSION
2.08	2.50

FULL ESTIMATED COST

FILE 'CAPLUS' ENTERED AT 11:27:56 ON 22 SEP 2003
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FILE 'USPATFULL' ENTERED AT 11:27:56 ON 22 SEP 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s 14

L5 19 L4

=> s 15 and (photoresist or resist)

L6 4 L5 AND (PHOTORESIST OR RESIST)

=> d 16 1-4 ibib hitstr abs

L6 ANSWER 1 OF 4 CAPLUS COPYRIGHT 2003 ACS on STN

ACCESSION NUMBER: 2002:397839 CAPLUS

DOCUMENT NUMBER: 136:409059

TITLE: Fluorine-containing cycloolefin polymer,
photoresist material containing the polymer,
and formation of pattern

INVENTOR(S): Hatakeyama, Jun; Watanabe, Atsushi; Harada, Yuji;
Kawai, Yoshio; Sasako, Masaru; Endo, Masataka;
Kishimura, Shinji; Otani, Michitaka; Miyazawa, Satoru;

PATENT ASSIGNEE(S): Tsutsumi, Kentaro; Maeda, Kazuhiko
Shin-Etsu Chemical Industry Co., Ltd., Japan;
Matsushita Electric Industrial Co., Ltd.; Central
Glass Co., Ltd.

SOURCE: Jpn. Kokai Tokkyo Koho, 25 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

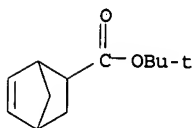
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002155120	A2	20020528	JP 2001-266772	20010904
PRIORITY APPLN. INFO.: IT 430427-86-4P			JP 2000-271209 A	20000907

RL: IMF (Industrial manufacture); TEM (Technical or engineered material
use); PREP (Preparation); USES (Uses)
(fluorine-contg. cycloolefin polymer for (chem.-amplified) pos.-working
photoresist)

RN 430427-86-4 CAPLUS
 CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester,
 polymer with 2,5-furandione and octafluorocyclopentene (9CI) (CA INDEX
 NAME)

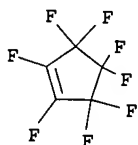
CM 1

CRN 154970-45-3
 CMF C12 H18 O2



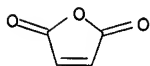
CM 2

CRN 559-40-0
 CMF C5 F8

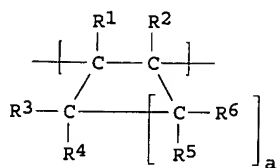


CM 3

CRN 108-31-6
 CMF C4 H2 O3



GI



I

AB The polymer has a cycloolefin-derived repeating unit I (R1-R6 = H, F, Cl, C1-20 linear, branched, or cyclic alkyl, fluorinated alkyl; .gtoreq.1 of R1-R6 contain F; 0.ltoreq. a .ltoreq.10) and another repeating unit having an acid-unstable group. The photoresist contains the polymer and an org. solvent and an acid-generating agent may be further added to the compn. to give a chem.-amplified pos.-working photoresist. The compn. is applied on a substrate, heated, exposed to high energy beam at 110-190 nm or 1-15 nm wavelength through a photomask, and developed optionally after heating to give a pattern. The photoresist shows enhanced transparency to vacuum UV rays and dry etching resistance.

L6 ANSWER 2 OF 4 CAPLUS COPYRIGHT 2003 ACS on STN

ACCESSION NUMBER: 2001:864931 CAPLUS

DOCUMENT NUMBER: 136:12834

TITLE: Positive-working photoresist compositions
 for use under vacuum UV lasers and method for pattern
 formation

INVENTOR(S): Otani, Michitaka; Tsutsumi, Kentaro; Maeda, Kazuhiko

PATENT ASSIGNEE(S): Central Glass Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

11/30/01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001330955	A2	20011130	JP 2000-149968	20000522
PRIORITY APPLN. INFO.: JP 2000-149968 20000522				

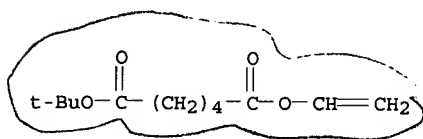
IT 374923-68-9P, tert-Butyl vinyl adipate-octafluorocyclopentene copolymer
 RL: IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PREP (Preparation); PROC (Process); USES (Uses)
 (pos.-working perfluorocyclopentene-vinyl copolymer compns. for lithog. imaging by irradiation of vacuum UV)

RN 374923-68-9 CAPLUS

CN Hexanedioic acid, 1,1-dimethylethyl ethenyl ester, polymer with octafluorocyclopentene (9CI) (CA INDEX NAME)

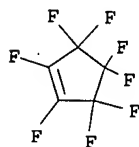
CM 1

CRN 374923-67-8
 CMF C12 H20 O4

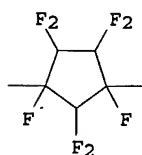


CM 2

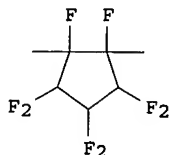
CRN 559-40-0
 CMF C5 F8



GI



I



II

AB The compns. comprise fluoropolymers which change soly against aq. alk. soln. by reaction with acids and acid generators. The polymers consist of .gtoreq.1 mol% of structural repeating units I or II and .ltoreq.99 mol% monomers derived from vinyl compds. Preferable comonomers are also given in Markush structures. Formation of pattern is carried out by application of the compn. on a substrate, patterned exposure of the resist layer with light having wavelength 1-190 nm, and development of the irradiated layer. The compns. have high transparency against vacuum UV (VUV), esp. against F₂ excimer lasers, and have high sensitivity.

L6 ANSWER 3 OF 4 HCAPLUS COPYRIGHT 2003 ACS on STN

ACCESSION NUMBER: 2002:397839 HCAPLUS

DOCUMENT NUMBER: 136:409059

TITLE: Fluorine-containing cycloolefin polymer, photoresist material containing the polymer, and formation of pattern

INVENTOR(S): Hatakeyama, Jun; Watanabe, Atsushi; Harada, Yuji;

Kawai, Yoshio; Sasako, Masaru; Endo, Masataka;
 Kishimura, Shinji; Otani, Michitaka; Miyazawa, Satoru;
 Tsutsumi, Kentaro; Maeda, Kazuhiko
 PATENT ASSIGNEE(S): Shin-Etsu Chemical Industry Co., Ltd., Japan;
 Matsushita Electric Industrial Co., Ltd.; Central
 Glass Co., Ltd.
 SOURCE: Jpn. Kokai Tokkyo Koho, 25 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

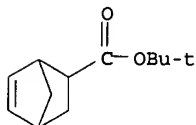
5/28/02

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002155120	A2	20020528	JP 2001-266772	20010904
PRIORITY APPLN. INFO.:			JP 2000-271209	A 20000907

IT 430427-86-4P
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material
 use); PREP (Preparation); USES (Uses)
 (fluorine-contg. cycloolefin polymer for (chem.-amplified) pos.-working
 photoresist)
 RN 430427-86-4 HCAPLUS
 CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester,
 polymer with 2,5-furandione and octafluorocyclopentene (9CI) (CA INDEX
 NAME)

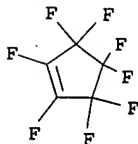
CM 1

CRN 154970-45-3
 CMF C12 H18 O2



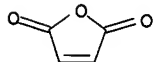
CM 2

CRN 559-40-0
 CMF C5 F8

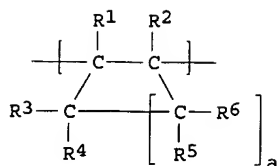


CM 3

CRN 108-31-6
 CMF C4 H2 O3



GI



I

AB The polymer has a cycloolefin-derived repeating unit I (R1-R6 = H, F, Cl, C1-20 linear, branched, or cyclic alkyl, fluorinated alkyl; .gtoreq.1 of R1-R6 contain F; 0.1toreq. a .ltoreq.10) and another repeating unit having an acid-unstable group. The photoresist contains the polymer and an org. solvent and an acid-generating agent may be further added to the compn. to give a chem.-amplified pos.-working photoresist. The compn. is applied on a substrate, heated, exposed to high energy beam at 110-190 nm or 1-15 nm wavelength through a photomask, and developed optionally after heating to give a pattern. The photoresist shows enhanced transparency to vacuum UV rays and dry etching resistance.

L6 ANSWER 4 OF 4 HCAPLUS COPYRIGHT 2003 ACS on STN

ACCESSION NUMBER: 2001:864931 HCAPLUS

DOCUMENT NUMBER: 136:12834

TITLE: Positive-working photoresist compositions for use under vacuum UV lasers and method for pattern formation

INVENTOR(S): Otani, Michitaka; Tsutsumi, Kentaro; Maeda, Kazuhiko

PATENT ASSIGNEE(S): Central Glass Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001330955	A2	20011130	JP 2000-149968	20000522
PRIORITY APPLN. INFO.:			JP 2000-149968	20000522

IT 374923-68-9P, tert-Butyl vinyl adipate-octafluorocyclopentene copolymer

RL: IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PREP (Preparation); PROC (Process); USES (Uses)

(pos.-working perfluorocyclopentene-vinyl copolymer compns. for lithog. imaging by irradiation of vacuum UV)

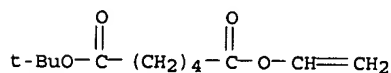
RN 374923-68-9 HCAPLUS

CN Hexanedioic acid, 1,1-dimethylethyl ethenyl ester, polymer with octafluorocyclopentene (9CI) (CA INDEX NAME)

CM 1

CRN 374923-67-8

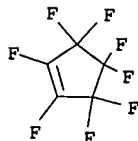
CMF C12 H20 O4



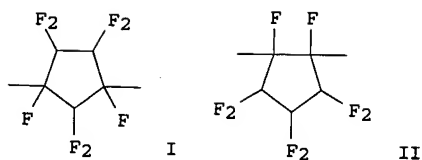
CM 2

CRN 559-40-0

CMF C5 F8



GI



AB The compns. comprise fluoropolymers which change soly against aq. alk. soln. by reaction with acids and acid generators. The polymers consist of .gtoreq.1 mol% of structural repeating units I or II and .ltoreq.99 mol% monomers derived from vinyl compds. Preferable comonomers are also given in Markush structures. Formation of pattern is carried out by application of the compn. on a substrate, patterned exposure of the resist layer with light having wavelength 1-190 nm, and development of the irradiated layer. The compns. have high transparency against vacuum UV (VUV), esp. against F2 excimer lasers, and have high sensitivity.

PROJECTED ITERATIONS: 536511 TO 556249
PROJECTED ANSWERS: 649 TO 1535

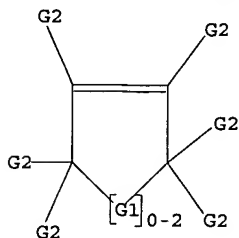
L10 2 SEA SSS SAM L8 AND L7

=> d 19

L9 HAS NO ANSWERS

L7 SCR 2067

L8 STR



G1 CF2,CBr2,CI2

G2 CF2,CF3,CCl2,CCl3,CBr2,CBr3,CI2,CI3,Cl,Br,F,I,X

Structure attributes must be viewed using STN Express query preparation.
L9 QUE ABB=ON PLU=ON L8 AND L7

=> d 110

L10 ANSWER 1 OF 2 REGISTRY COPYRIGHT 2003 ACS on STN

RN 430427-86-4 REGISTRY

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester,
polymer with 2,5-furandione and octafluorocyclopentene (9CI) (CA INDEX
NAME)

MF (C12 H18 O2 . C5 F8 . C4 H2 O3)x

CI PMS

PCT Polyether, Polyvinyl

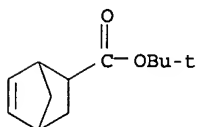
SR CA

LC STN Files: CA, CAPLUS

CM 1

CRN 154970-45-3

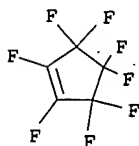
CMF C12 H18 O2



CM 2

CRN 559-40-0

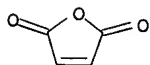
CMF C5 F8



CM 3

CRN 108-31-6

CMF C4 H2 O3



1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> FIL CAPLUS HCAPLUS USPATFUL
COST IN U.S. DOLLARS

SINCE FILE ENTRY	TOTAL SESSION
2.08	31.49

FULL ESTIMATED COST

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)

SINCE FILE ENTRY	TOTAL SESSION
0.00	-2.60

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FILE 'HCAPLUS' ENTERED AT 11:32:38 ON 22 SEP 2003
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FILE 'USPATFULL' ENTERED AT 11:32:38 ON 22 SEP 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s l10

L11 5 L10

=> d his

(FILE 'HOME' ENTERED AT 11:26:15 ON 22 SEP 2003)

FILE 'REGISTRY' ENTERED AT 11:27:08 ON 22 SEP 2003

L1 SCREEN 2067
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
L4 7 S L3 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL' ENTERED AT 11:27:56 ON 22 SEP 2003

L5 19 S L4
L6 4 S L5 AND (PHOTORESIST OR RESIST)

FILE 'HOME' ENTERED AT 11:29:06 ON 22 SEP 2003

FILE 'REGISTRY' ENTERED AT 11:31:41 ON 22 SEP 2003

L7 SCREEN 2067
L8 STRUCTURE UPLOADED
L9 QUE L8 AND L7

FILE 'REGISTRY' ENTERED AT 11:32:10 ON 22 SEP 2003

L10 2 S L9 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL' ENTERED AT 11:32:38 ON 22 SEP 2003

L11 5 S L10

=> s l11 not 16

L12 3 L11 NOT L6

=> d l12 1-3 ibib hitstr abs

L12 ANSWER 1 OF 3 CAPLUS COPYRIGHT 2003 ACS on STN

ACCESSION NUMBER: 2001:326291 CAPLUS

DOCUMENT NUMBER: 134:341129

TITLE: Fluoropolymers having saturated perfluoro rings with good solubility in organic solvents and their manufacture

INVENTOR(S): Akama, Hidehiro; Sugimoto, Hiromi; Tsutsumi, Kentaro

PATENT ASSIGNEE(S): Central Glass Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

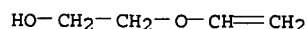
LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 2

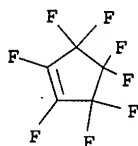
PATENT INFORMATION:

5/8/01

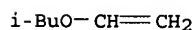
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001122928	A2	20010508	JP 2000-232570	20000801
PRIORITY APPLN. INFO.: JP 1999-231687 A 19990818				
IT 337488-50-3P, Hydroxyethyl vinyl ether-isobutyl vinyl ether-octafluorocyclopentene copolymer				
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)				
(manuf. of fluoropolymers having satd. perfluoro rings with good soly. in org. solvents for transparent films)				
RN	337488-50-3 CAPLUS			
CN	Ethanol, 2-(ethenyloxy)-, polymer with 1-(ethenyloxy)-2-methylpropane and octafluorocyclopentene (9CI) (CA INDEX NAME)			
CM	1			
CRN	764-48-7			
CMF	C4 H8 O2			



CM 2
CRN 559-40-0
CMF C5 F8



CM 3
CRN 109-53-5
CMF C6 H12 O



AB The fluoropolymers (av. mol. wt. 1000-1,000,000; measured by gel permeation chromatog.), useful for transparent films, coatings, etc., contain repeating units of (A) 1-99 mol% 1,3- or 1,2-perfluorocyclopentylene and (B) 1-99 mol% divalent org. groups. Thus, an acetone soln. of vinyl acetate-octafluorocyclopentene copolymer was applied on a glass plate and dried to give a transparent film.

L12 ANSWER 2 OF 3 HCAPLUS COPYRIGHT 2003 ACS on STN
ACCESSION NUMBER: 2001:326291 HCAPLUS
DOCUMENT NUMBER: 134:341129
TITLE: Fluoropolymers having saturated perfluoro rings with good solubility in organic solvents and their manufacture
INVENTOR(S): Akama, Hidehiro; Sugimoto, Hiromi; Tsutsumi, Kentaro
PATENT ASSIGNEE(S): Central Glass Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 2
PATENT INFORMATION:

5/8/01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001122928	A2	20010508	JP 2000-232570	20000801
PRIORITY APPLN. INFO.: JP 1999-231687 A 19990818				
IT 337488-50-3P, Hydroxyethyl vinyl ether-isobutyl vinyl ether-octafluorocyclopentene copolymer				
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)				

(manuf. of fluoropolymers having satd. perfluoro rings with good soly.
in org. solvents for transparent films)

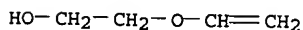
RN 337488-50-3 HCAPLUS

CN Ethanol, 2-(ethenyloxy)-, polymer with 1-(ethenyloxy)-2-methylpropane and
octafluorocyclopentene (9CI) (CA INDEX NAME)

CM 1

CRN 764-48-7

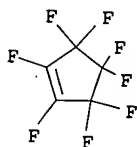
CMF C4 H8 O2



CM 2

CRN 559-40-0

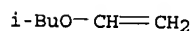
CMF C5 F8



CM 3

CRN 109-53-5

CMF C6 H12 O



AB The fluoropolymers (av. mol. wt. 1000-1,000,000; measured by gel permeation chromatog.), useful for transparent films, coatings, etc., contain repeating units of (A) 1-99 mol% 1,3- or 1,2-perfluorocyclopentylene and (B) 1-99 mol% divalent org. groups. Thus, an acetone soln. of vinyl acetate-octafluorocyclopentene copolymer was applied on a glass plate and dried to give a transparent film.

L12 ANSWER 3 OF 3 USPATFULL on STN

ACCESSION NUMBER: 2002:137125 USPATFULL

TITLE: Fluorine-containing copolymer and composition for preparing low reflectance film

INVENTOR(S): Akama, Shuyo, Saitama, JAPAN
Sugimoto, Hiromi, Saitama, JAPAN
Tsutsumi, Kentaro, Saitama, JAPAN

PATENT ASSIGNEE(S): Central Glass Company, Limited, Ube, JAPAN (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6403744	B1	20020611
APPLICATION INFO.:	US 2000-640536		20000817 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-231687	19990818
	JP 2000-84628	20000324

DOCUMENT TYPE: Utility

FILE SEGMENT: GRANTED

PRIMARY EXAMINER: Zitomer, Fred

LEGAL REPRESENTATIVE: Crowell & Moring LLP

NUMBER OF CLAIMS: 19

EXEMPLARY CLAIM: 1

NUMBER OF DRAWINGS: 6 Drawing Figure(s); 6 Drawing Page(s)

LINE COUNT: 954

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 337488-50-3P, Hydroxyethyl vinyl ether-isobutyl vinyl
ether-octafluorocyclopentene copolymer

(manuf. of fluoropolymers having satd. perfluoro rings with good soly.
in org. solvents for transparent films)

6/11/02

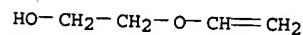
8/17/00 ✓

102(e)

RN 337488-50-3 USPATFULL
CN Ethanol, 2-(ethenyloxy)-, polymer with 1-(ethenyloxy)-2-methylpropane and octafluorocyclopentene (9CI) (CA INDEX NAME)

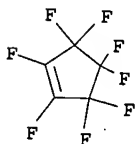
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CRN 764-48-7
CMF C4 H8 O2



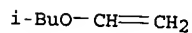
CM 2

CRN 559-40-0
CMF C5 F8



CM 3

CRN 109-53-5
CMF C6 H12 O



AB The invention relates to a fluorine-containing copolymer. This copolymer contains 1-99 mol % of a special first repeating unit of a cyclic perfluoro group; and 99-1 mol % of a second repeating unit of a bivalent organic group. The copolymer has a number average molecular weight of from 1,000 to 1,000,000 determined in a gel permeation chromatography using polystyrene as a standard material thereof. The invention further relates to a composition for forming a low reflectance film. This composition contains as a film-forming component a fluorine-containing polymer containing the first repeating unit. This polymer can be the above copolymer. A film formed by applying the composition to a substrate provides low reflectance and is improved in hardness.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

=> file reg		
COST IN U.S. DOLLARS	SINCE FILE	TOTAL
	ENTRY	SESSION
FULL ESTIMATED COST	0.21	0.21

FILE 'REGISTRY' ENTERED AT 11:34:17 ON 22 SEP 2003
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Property values tagged with IC are from the ZIC/VINITI data file provided by InfoChem.

STRUCTURE FILE UPDATES: 21 SEP 2003 HIGHEST RN 590345-44-1
 DICTIONARY FILE UPDATES: 21 SEP 2003 HIGHEST RN 590345-44-1

TSCA INFORMATION NOW CURRENT THROUGH JULY 14, 2003

Please note that search-term pricing does apply when conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. See HELP PROPERTIES for more information. See STNote 27, Searching Properties in the CAS Registry File, for complete details:
<http://www.cas.org/ONLINE/STN/STNOTES/stnotes27.pdf>

=> s octafluorocyclopentene
 0 OCTAFLUOROCYCLOPENTENE
 L1 0 OCTAFLUOROCYCLOPENTENE

=> s octafluoropentane
 L2 41 OCTAFLUOROPENTANE

=> s hexafluorocyclopentene
 L3 20 HEXAFLUOROCYCLOPENTENE

=> s hexafluorocyclobutene
 L4 15 HEXAFLUOROCYCLOBUTENE

=> s octafluorocyclopentene
 L5 37 OCTAFLUOROCYCLOPENTENE

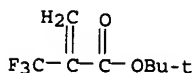
=> s l2 or l4 or l5
 L6 90 L2 OR L4 OR L5

=> d

L6 ANSWER 1 OF 90 REGISTRY COPYRIGHT 2003 ACS on STN
 RN 568587-28-0 REGISTRY
 CN 2-Propenoic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer with (ethenyloxy)cyclohexane, octafluorocyclopentene and 2,2,2-trifluoro-1-(trifluoromethyl)ethyl 2-(trifluoromethyl)-2-propenoate (9CI) (CA INDEX NAME)
 MF (C8 H14 O . C8 H11 F3 O2 . C7 H3 F9 O2 . C5 F8)x
 CI PMS
 PCT Polyacrylic, Polyether, Polyvinyl
 SR CA
 LC STN Files: CA, CAPLUS

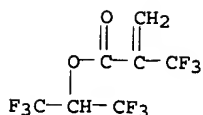
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CRN 105935-24-8
 CMF C8 H11 F3 O2



CM 2

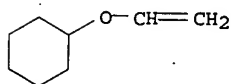
CRN 91520-41-1
 CMF C7 H3 F9 O2



CM 3

CRN 2182-55-0

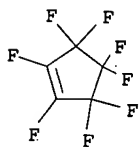
CMF C8 H14 O



CM 4

CRN 559-40-0

CMF C5 F8



1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> FIL CAPLUS HCAPLUS USPATFUL
COST IN U.S. DOLLARS

SINCE FILE
ENTRY
23.98

TOTAL
SESSION
24.19

FULL ESTIMATED COST

FILE 'CAPLUS' ENTERED AT 11:35:57 ON 22 SEP 2003
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FILE 'HCAPLUS' ENTERED AT 11:35:57 ON 22 SEP 2003
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
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FILE 'USPATFULL' ENTERED AT 11:35:57 ON 22 SEP 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s 16

L7 1620 L6

=> s 17 and (photoresist or resist)

L8 143 L7 AND (PHOTORESIST OR RESIST)

=> s 18 and (?acid (w) generator)

L9 15 L8 AND (?ACID (W) GENERATOR)

=> s 19 and solvent

L10 7 L9 AND SOLVENT

=> duplicates remove l10

DUPLICATE PREFERENCE IS 'CAPLUS, HCAPLUS, USPATFULL'

KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n

PROCESSING COMPLETED FOR L10

L11 3 DUPLICATE REMOVE L10 (4 DUPLICATES REMOVED)

=> d l11 1-3 ibib hitstr

L11 ANSWER 1 OF 3 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 1
ACCESSION NUMBER: 2003:77400 CAPLUS

DOCUMENT NUMBER: 138:145061
 TITLE: Photoresist monomers, polymers thereof and photoresist compositions containing the same
 INVENTOR(S): Lee, Geun Su; Jung, Jae Chang; Shin, Ki Soo
 PATENT ASSIGNEE(S): S. Korea
 SOURCE: U.S. Pat. Appl. Publ., 12 pp.
 CODEN: USXXCO
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO. KIND DATE APPLICATION NO. DATE

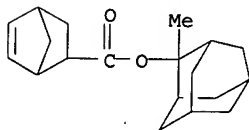
 US 2003022101 A1 20030130 US 2002-80319 20020221
 PRIORITY APPLN. INFO.: KR 2001-38026 A 20010629
 OTHER SOURCE(S): MARPAT 138:145061

IT 492469-83-7P 492469-85-9P 492469-88-2DP,
 4-Acetoxystyrene-hexafluorocyclobutene copolymer, hydrolyzed and reaction
 product with ethylvinylether
 RL: SPN (Synthetic preparation); TEM (Technical or engineered material
 use); PREP (Preparation); USES (Uses)
 (photoresist monomers and polymers for photoresist
 compns.)

RN 492469-83-7 CAPLUS
 CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-
 methyltricyclo[3.3.1.1^{3,7}]dec-2-yl ester, polymer with
 hexafluorocyclobutene (9CI) (CA INDEX NAME)

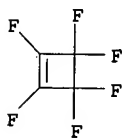
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CRN 328087-85-0
 CMF C19 H26 O2



CM 2

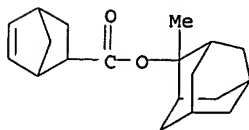
CRN 697-11-0
 CMF C4 F6



RN 492469-85-9 CAPLUS
 CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-
 methyltricyclo[3.3.1.1^{3,7}]dec-2-yl ester, polymer with
 2-ethyltricyclo[3.3.1.1^{3,7}]dec-2-yl 2-propenoate and
 octafluorocyclopentene (9CI) (CA INDEX NAME)

CM 1

CRN 328087-85-0
 CMF C19 H26 O2

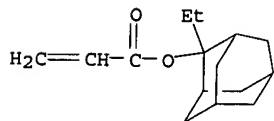


CM 2

2/21/02
 present
 application

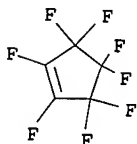
1/30/03

CRN 303186-14-3
CMF C15 H22 O2



CM 3

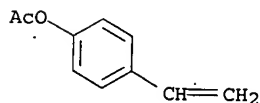
CRN 559-40-0
CMF C5 F8



RN 492469-88-2 CAPLUS
CN Phenol, 4-ethenyl-, acetate, polymer with hexafluorocyclobutene (9CI) (CA
INDEX NAME)

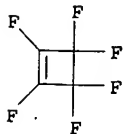
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CRN 2628-16-2
CMF C10 H10 O2



CM 2

CRN 697-11-0
CMF C4 F6



L11 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 2
ACCESSION NUMBER: 2003:5311 CAPLUS
DOCUMENT NUMBER: 138:63829
TITLE: Photoresist monomers, polymers thereof and
photoresist compositions containing the same
INVENTOR(S): Lee, Geun Su; Jung, Jae Chang; Shin, Ki Soo
PATENT ASSIGNEE(S): S. Korea
SOURCE: U.S. Pat. Appl. Publ., 13 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2003003379	A1	20030102	US 2002-79348	20020220
JP 2003040931	A2	20030213	JP 2002-122435	20020424

*Not
to
another!*

2/20/02

PRIORITY APPLN. INFO.:

IT 559-40-0

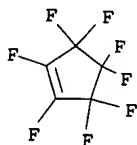
KR 2001-34603

A 20010619

RL: RCT (Reactant); RACT (Reactant or reagent)
(prepn. fluoropolymer for photoresist compns.)

RN 559-40-0 CAPLUS

CN Cyclopentene, octafluoro- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)



L11 ANSWER 3 OF 3 USPATFULL on STN

ACCESSION NUMBER: 2003:10537 USPATFULL

TITLE: Polymers, resist compositions and patterning process

INVENTOR(S): Harada, Yuji, Nakakubiki-gun, JAPAN
Watanabe, Jun, Nakakubiki-gun, JAPAN
Hatakeyama, Jun, Nakakubiki-gun, JAPAN
Kawai, Yoshio, Nakakubiki-gun, JAPAN
Sasago, Masaru, Hirakata-shi, JAPAN
Endo, Masayuki, Izumi-shi, JAPAN
Kishimura, Shinji, Itami-shi, JAPAN
Ootani, Michitaka, Kawagoe-shi, JAPAN
Miyazawa, Satoru, Kawagoe-shi, JAPAN
Tsutsumi, Kentaro, Kawagoe-shi, JAPAN
Maeda, Kazuhiko, Chiyoda-ku, JAPAN

PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Tokyo, JAPAN (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003008231	A1	20030109
APPLICATION INFO.:	US 2002-84828	A1	20020228 (10)

2/28/02

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2001-53664	20010228
	JP 2001-53669	20010228
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	MILLEN, WHITE, ZELANO & BRANIGAN, P.C., 2200 CLARENDON BLVD., SUITE 1400, ARLINGTON, VA, 22201	
NUMBER OF CLAIMS:	9	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1461	

not prior art

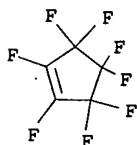
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 559-40-0, Octafluorocyclopentene

(F-contg. group-contg. polymers for chem. amplified pos.-working resists and their use in pattern formation)

RN 559-40-0 USPATFULL

CN Cyclopentene, octafluoro- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)



=> d 120 1-3 ibib hitstr

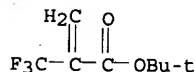
L20 ANSWER 1 OF 3 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 1
ACCESSION NUMBER: 2003:626408 CAPLUS
DOCUMENT NUMBER: 139:157393
TITLE: Fluorine-containing photoresist with
reaction anchor for chemical amplification and
improved copolymerization characteristics
INVENTOR(S): Rottstegge, Joerg
PATENT ASSIGNEE(S): Infineon Technologies A.-G., Germany
SOURCE: Ger. Offen., 14 pp.
CODEN: GWXXBX
DOCUMENT TYPE: Patent
LANGUAGE: German
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
DE 10203838	A1	20030814	DE 2002-10203838	20020131
US 2003157432	A1	20030821	US 2003-356791	20030131
PRIORITY APPLN. INFO.:			DE 2002-10203838 A	20020131

IT 572922-00-0P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material
use); PREP (Preparation); USES (Uses)
(fluorine-contg. photoresist with reaction anchor for chem.
amplification and improved copolymn. characteristics)
RN 572922-00-0 CAPLUS
CN 2-Propenoic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer
with decafluorocyclohexene and 3a,4,7,7a-tetrahydro-1,3-isobenzofurandione
(9CI) (CA INDEX NAME)

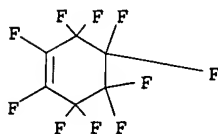
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CRN 105935-24-8
CMF C8 H11 F3 O2



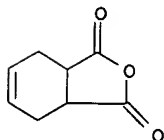
CM 2

CRN 355-75-9
CMF C6 F10



CM 3

CRN 85-43-8
CMF C8 H8 O3



L20 ANSWER 2 OF 3 USPATFULL on STN
ACCESSION NUMBER: 2003:225620 USPATFULL
TITLE: Fluorine-containing photoresist having
reactive anchors for chemical amplification and

INVENTOR(S): improved copolymerization properties
Rottstegge, Jorg, Lillenthal, GERMANY, FEDERAL REPUBLIC
OF

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003157432	A1	20030821
APPLICATION INFO.:	US 2003-356791	A1	20030131 (10)

	NUMBER	DATE
PRIORITY INFORMATION:	DE 2002-10203838	20020131
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	LERNER AND GREENBERG, P.A., POST OFFICE BOX 2480, HOLLYWOOD, FL, 33022-2480	
NUMBER OF CLAIMS:	14	
EXEMPLARY CLAIM:	1	
LINE COUNT:	871	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		

IT 572922-00-0P

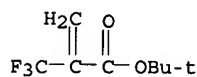
(fluorine-contg. photoresist with reaction anchor for chem.
amplification and improved copolymn. characteristics)

RN 572922-00-0 USPTFULL

CN 2-Propenoic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer
with decafluorocyclohexene and 3a,4,7,7a-tetrahydro-1,3-
isobenzofurandione (9CI) (CA INDEX NAME)

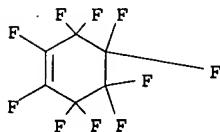
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CMF C8 H11 F3 O2



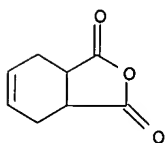
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CMF C6 F10



CM 3

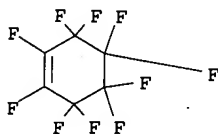
CRN 85-43-8
CMF C8 H8 O3



L20 ANSWER 3 OF 3 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 2
ACCESSION NUMBER: 2002:868986 CAPLUS
DOCUMENT NUMBER: 137:370796
TITLE: Radiation-sensitive polysiloxane resin composition
INVENTOR(S): Iwasawa, Haruo; Hayashi, Akihiro; Shimokawa, Tsutomu;
Yamamoto, Masafumi
PATENT ASSIGNEE(S): JSR Co., Ltd., Japan
SOURCE: PCT Int. Appl., 155 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent

LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2002090423	A1	20021114	WO 2002-JP4333	20020430
W:				
AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,				
CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH,				
GM, HR, HU, ID, IL, IN, IS, KE, KG, KR, KZ, LC, LK, LR, LS, LT,				
LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT,				
RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG,				
US, UZ, VN, YU, ZA, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM				
RW:				
GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AT, BE, CH,				
CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR,				
BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
JP 2003020335	A2	20030124	JP 2002-48643	20020225
PRIORITY APPLN. INFO.:			JP 2001-133795	A 20010501
			JP 2002-48643	A 20020225
OTHER SOURCE(S):		MARPAT 137:370796		
IT 355-75-9, Decafluorocyclohexene				
RL: RCT (Reactant); RACT (Reactant or reagent)				
(radiation-sensitive polysiloxane resin compn.)				
RN 355-75-9 CAPLUS				
CN Cyclohexene, decafluoro- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)				



REFERENCE COUNT: 25 THERE ARE 25 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

=>